

Atty. Dkt. No. 039153-0306 (F0793)

1 1. (Cancelled) A lithographic system for an integrated circuit
2 fabrication process, the lithographic system comprising:
3 a computer; and
4 a configurable mask or reticle coupled to the computer,
5 wherein the configurable mask or reticle allows light to be transmitted in a
6 pattern controlled by a control signal from the computer.

1 2. (Cancelled) The lithographic system of claim 1, wherein the
2 configurable mask or reticle is an LCD or LED matrix.

1 3. (Cancelled) The lithographic system of claim 1 further
2 comprising:
3 a database for providing image information associated with a
4 device to be patterned on a wafer, the computer using the image
5 information to generate the control signal.

1 4. (Cancelled) The lithographic system of claim 3, wherein the
2 database is stored on a storage media.

1 5. (Cancelled) The lithographic system of claim 3, wherein the
2 image information is related to transistor structures.

1 6. (Cancelled) The lithographic system of claim 1, wherein the
2 control signal is a video signal.

1 7. (Currently Amended) A method of manufacturing an
2 integrated circuit, the method comprising:
3 providing a pattern of radiation via an LCD or LED assembly
4 In response to a control signal from a computer, the computer generating
5 the control signal in response to image data stored in a database, the

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cont.

6 computer generating component data from the image data to generate the
7 control signal; and
8 performing a semiconductor fabrication process in
9 accordance with the pattern of radiation.

1 8. (Original) The method of claim 7, further comprising:
2 providing a second pattern of radiation via the LCD or LED
3 assembly; and
4 performing a second semiconductor fabrication process in
5 accordance with the second pattern of radiation.

1 9. (Original) The method of claim 7, wherein the pattern is
2 provided to a wafer in a step and repeat process.

1 10. (Original) The method of claim 7, wherein the pattern is
2 representative of a metal layer associated with the integrated circuit.

1 11. (Original) The method of claim 7, wherein the pattern is
2 representative of a structure associated with a transistor for the integrated
3 circuit.

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1 12. (Currently Amended) The method of claim 7, wherein a
2 ~~representation of the pattern is stored electronically~~ the component data is
3 related to interconnect layers.

1 13. (Original) The method of claim 7, wherein the integrated
2 circuit is an ASIC.

1 14. (Original) The method of claim 7, wherein the pattern is
2 provided via the LCD assembly.

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1 15. (Cancelled) A pattern generator for an integrated circuit
2 fabrication system, the pattern generator comprising:
3 means for providing a pattern of light; and
4 means for controlling the means for providing, wherein the
5 means for controlling selects the pattern.

1 16. (Cancelled) The pattern generator of claim 15, further
2 comprising:
3 means for providing a light through the means for providing a
4 pattern.

1 17. (Cancelled) The pattern generator of claim 16, further
2 comprising:
3 means for focusing the light on a wafer.

1 18. (Cancelled) The pattern generator of claim 15, further
2 comprising:
3 means for storing elements, wherein the means for
4 controlling creates a control signal representative of the pattern in
5 response to the elements.

1 19. (Cancelled) The pattern generator of claim 15, wherein the
2 means for controlling includes a workstation executing a software
3 program.

1 20. (Cancelled) The pattern generator of claim 19, wherein the
2 means for providing a pattern includes liquid crystals.

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Please add the following new claims 21-32:

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1 21. (New) A method of using a pattern generator for an
2 integrated circuit fabrication system, the method comprising:
3 providing a pattern of radiation via an LCD assembly in
4 response to a control signal from a computer, the computer generating the
5 control signal in response to image data stored in a database, the
6 computer generating component data from the image data to generate the
7 control signal; and
8 performing a semiconductor fabrication process in
9 accordance with the pattern of radiation.

1 22. (New) The method of claim 21, wherein the pattern is for an
2 ASIC device.

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1 23. (New) The method of claim 22, wherein in the pattern
2 generator further comprises:
3 means for providing a pattern of light;
4 means for controlling the means for providing, wherein the
5 means for controlling selects the pattern; and
6 means for focusing the light on a wafer.

1 24. (New) The method of claim 15, wherein the image data are
2 shapes representing component interconnects.

1 25. (New) The method of claim 23, wherein the means for
2 controlling includes a workstation executing a software program.

1 26. (New) The method of claim 25, wherein the means for
2 providing a pattern includes liquid crystals.

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1 27. (New) In a lithographic system for an integrated circuit
2 fabrication process, the lithographic system including a computer and a
3 configurable mask or reticle coupled to the computer, wherein the
4 configurable mask or reticle allows light to be transmitted in a pattern
5 controlled by a control signal from the computer, a method comprising:
6 providing a pattern of radiation via the configurable mask or
7 reticle in response to a control signal from a computer, the computer
8 generating the control signal in response to image data stored in a
9 database, the computer using component data from the image data to
10 generate the control signal; and
11 performing a semiconductor fabrication process in
12 accordance with the pattern of radiation.

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cont.

1 28. (New) The method of claim 27, wherein the configurable
2 mask or reticle is an LCD or LED matrix.

1 29. (New) The method of claim 27 wherein the image data
2 includes ASIC information.

1 30. (New) The method of claim 29, wherein the database is
2 stored on a storage media.

1 31. (New) The method of claim 27, wherein the image data is
2 related to transistor structures.

1 32. (New) The method of claim 27, wherein the control signal is
2 a video signal.